

Apple A9 64-bit SoC

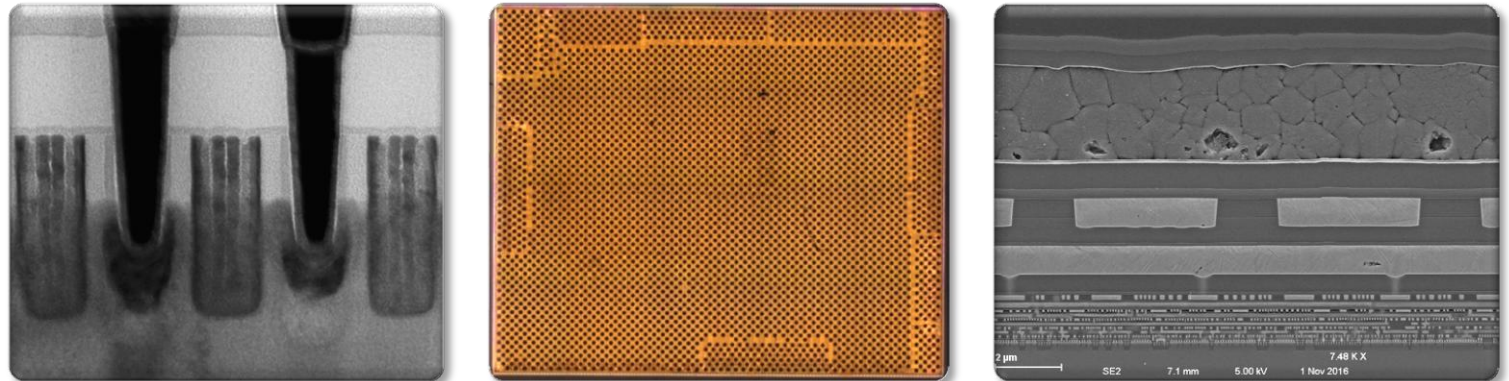
Apple 64-bit System-on Chip (FinFET 14nm)

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Product Analysis Report

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